

# Laser Phosphorous Doping at High Scan Rates for Crystalline Junction Formation in Silicon/Perovskite Tandem Solar Cells

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## Framework

- The monolithically integrated 2-Terminal Si/perovskite tandem solar cell is currently considered the future device by the PV community, having the potential overcome the efficiency of Si single junction devices [1];
- The two sub-cells can be electrically interconnected using a recombination T-junction that needs to be produced using scalable and reliable processes;
- A T-junction made of crystalline Si offers several advantages compared to amorphous Si and TCOs, namely the expected higher stability upon further deposition of the perovskite sub-cell;
- Here, we attempt shallow doping of Si at atmospheric pressure using an IR laser as the heating source for the formation of crystalline n<sup>++</sup> Si layers, giving the possibility of processing Si at speeds up to 5000 mm/s.

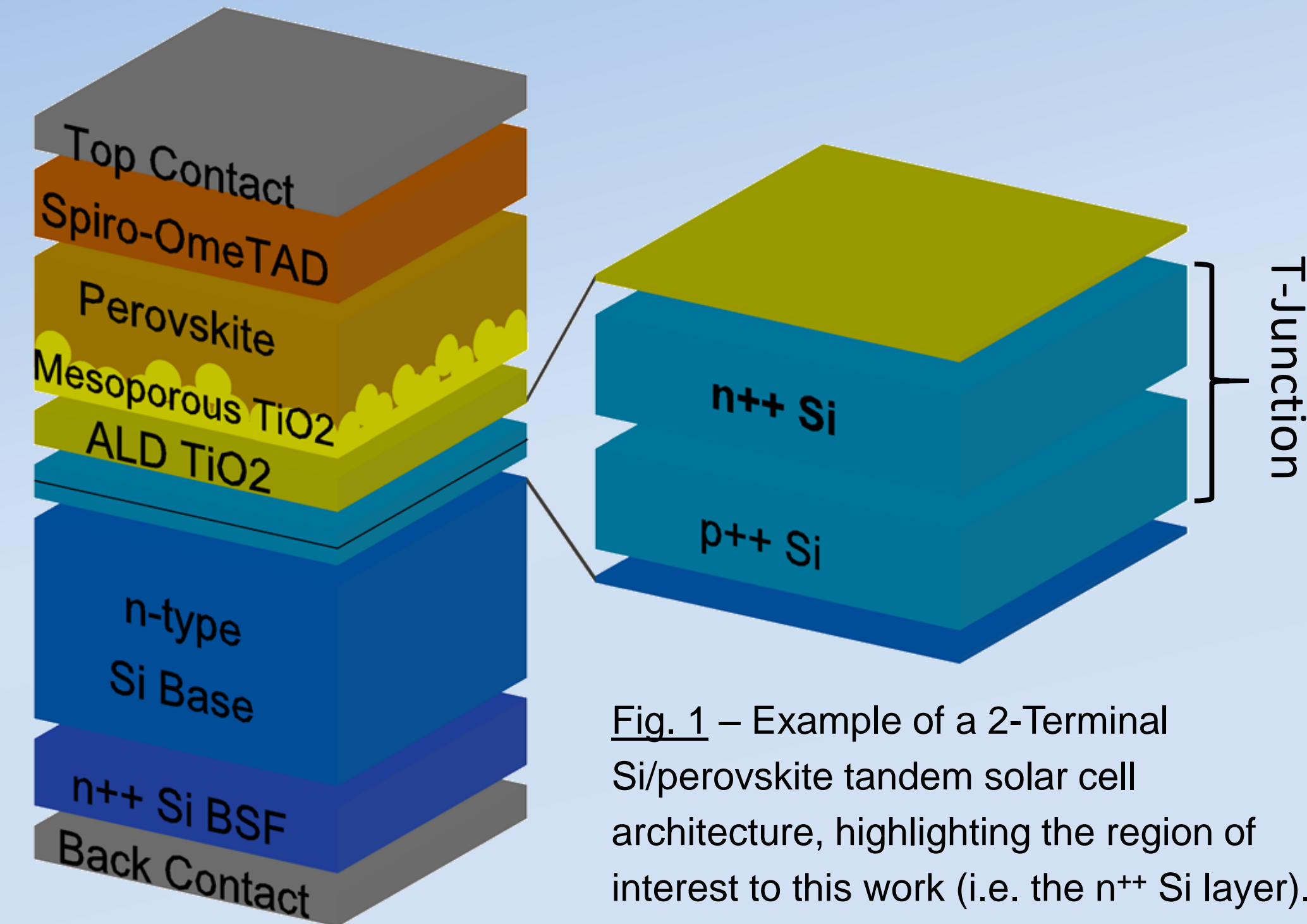


Fig. 1 – Example of a 2-Terminal Si/perovskite tandem solar cell architecture, highlighting the region of interest to this work (i.e. the n<sup>++</sup> Si layer).

## Laser doping setup

### Process flow

- Sample Loading
- Chamber Cleaning – purging and pumping cycles
- Setting chamber pressure to vacuum
- POCl<sub>3</sub>/Argon mixture flow into chamber
- Laser Rastering
- Chamber Cleaning – purging and pumping cycles
- Sample unloading and inspection

#### Sample details:

10 x 5 mm<sup>2</sup> areas were scanned on mirror-like Si using a constant energy density ( $E = 10.5 \text{ J/cm}^2$ ) with beam diameter of ca 20  $\mu\text{m}$  and a combination of other laser parameters:

- ✓ scan speed:  
 $v = [1000 - 5000] \text{ mm/s}$ ;
- ✓ distance between lines  
 $d = [40 - 5] \mu\text{m}$ ;
- ✓ number of scans:  
 $n = [1 - 3] \text{ times}$ ;

### Setup schematic

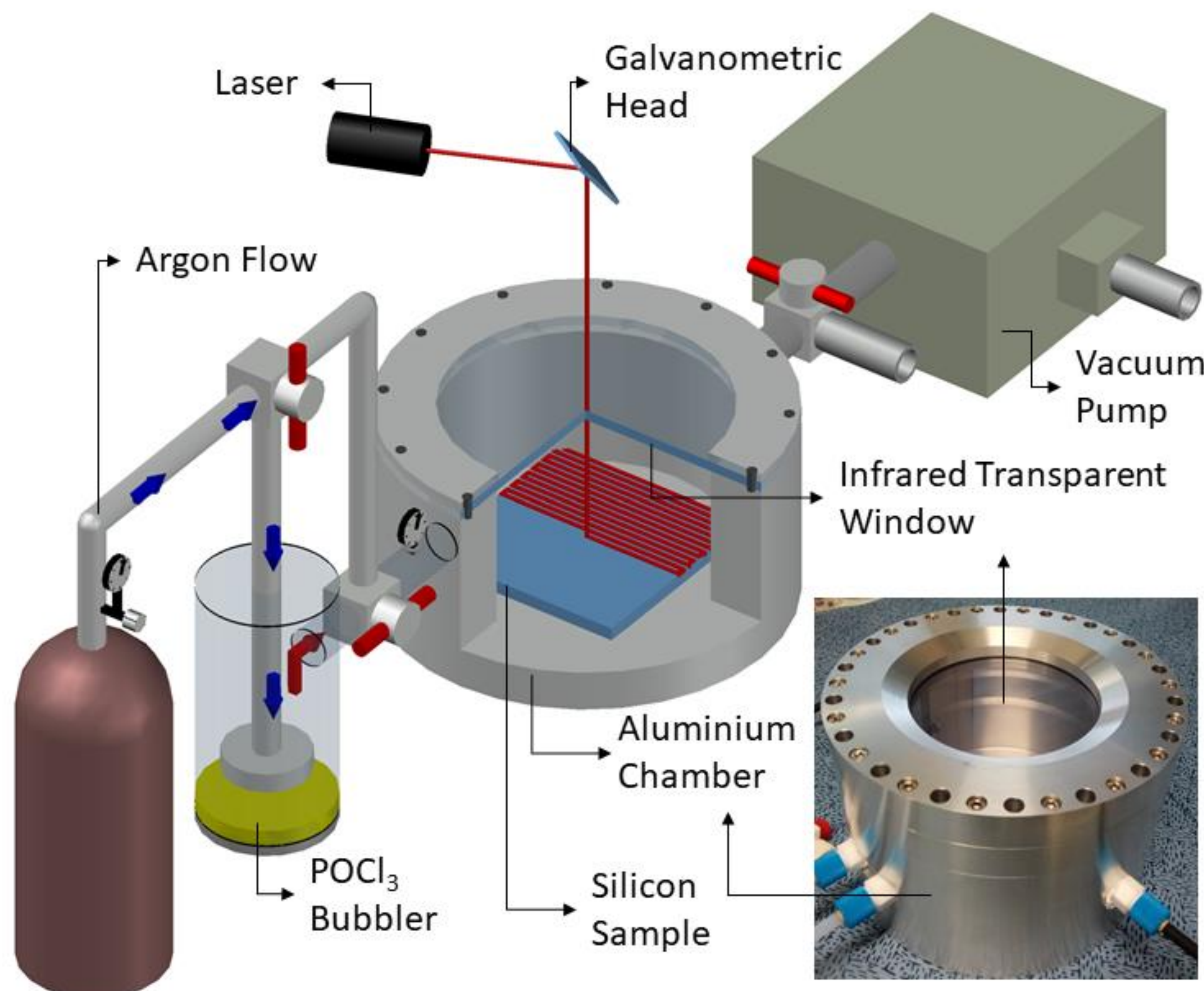


Fig. 2 – Schematic of laser doping apparatus developed to form tunnel junctions directly on p<sup>++</sup> Si emitters. Blue and red arrows correspond to Argon and POCl<sub>3</sub>/Argon mixture flows, respectively. A photo of the reaction chamber, with external diameter of 19 cm, is included on the bottom right-hand side of the schematic.

## Shallow silicon melting

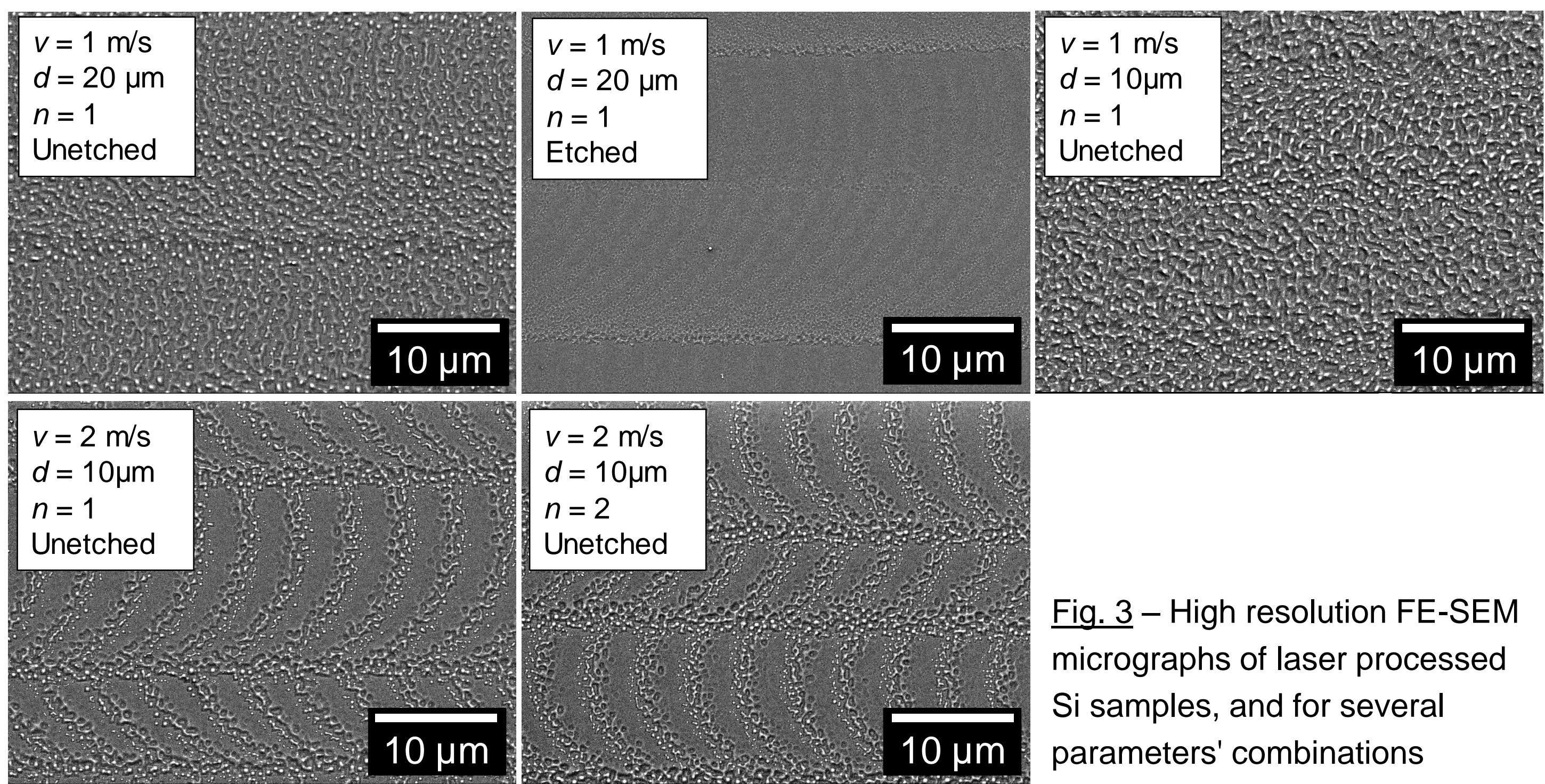


Fig. 3 – High resolution FE-SEM micrographs of laser processed Si samples, and for several parameters' combinations

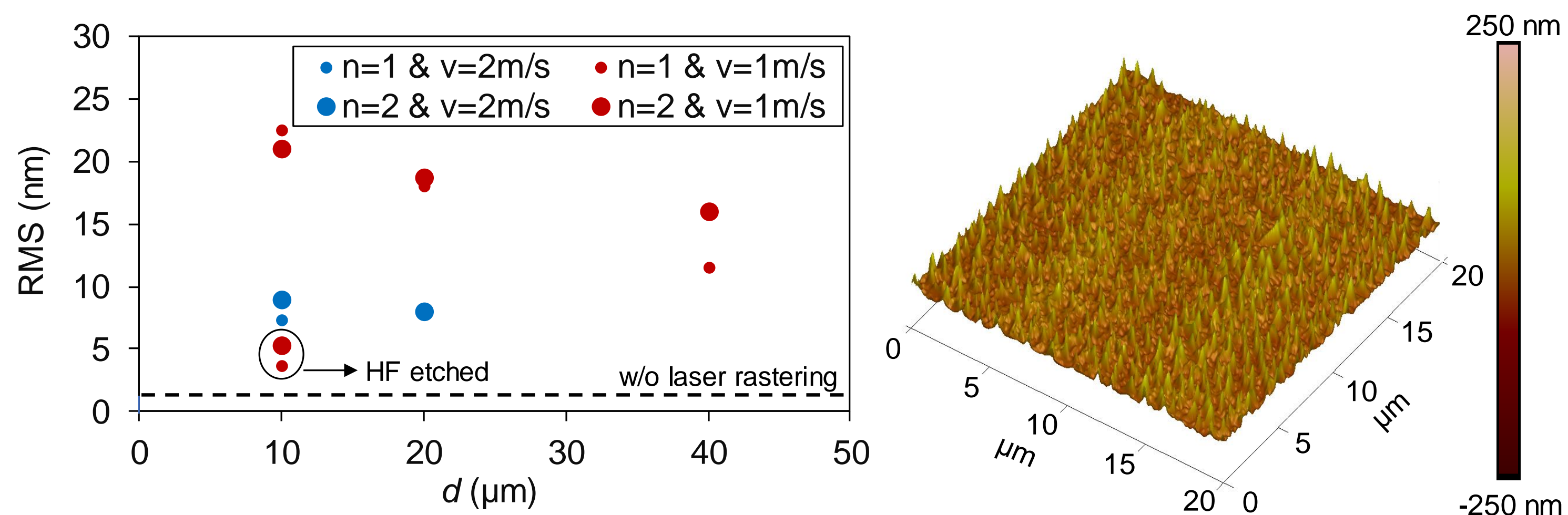


Fig. 4 – (left) Root mean square (RMS) as a function of  $d$  for different combinations of  $v$  and  $n$ , and sampling areas of 20 x 20  $\mu\text{m}^2$ . (right) AFM 3D image of processed sample at  $v = 1 \text{ m/s}$ ,  $d = 10 \mu\text{m}$  and  $n = 1$ .

## Phosphorus depth profiling

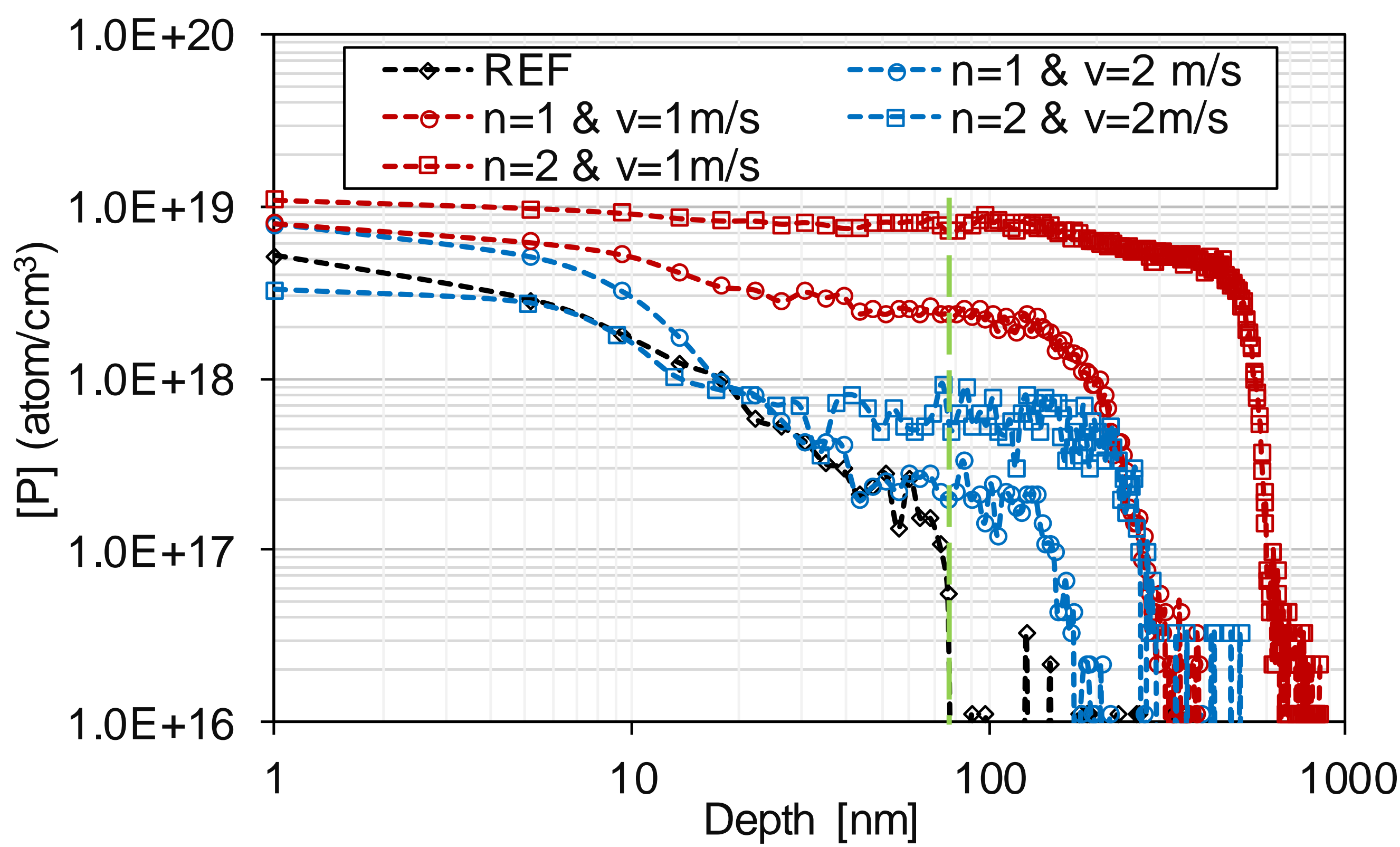


Fig. 5 - SIMS phosphorous depth profiles for unprocessed (REF) and laser processed samples at  $d = 10 \mu\text{m}$  and different combinations of  $v$  and  $n$ . Dashed green line delimits the POCl<sub>3</sub> adsorption at the surface.

## Remarks

- It was developed a setup that allowed shallow doping of Si wafers with phosphorous at the atmospheric pressure, as shown by AFM and SEM analyses;
- High phosphorous concentration was achieved, and preliminary SIMS data show a correlation between the laser processing parameters (e.g. number of scans) and the doping depth and peak concentration;
- Laser doping parameters must be further optimized to obtain thinner n<sup>++</sup> Si layers and reduce POCl<sub>3</sub> adsorption at the surface, while etch-back strategies must be developed.

[1] Z. Yu, M. Leilaoui, Z. Holman, "Selective tandem partners for silicon solar cells", *Nature Energy* (2016) 1, 16137, doi: 10.1038/nenergy.2016.137.

### Acknowledgements

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